AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

- (currently amended): A method for making three-dimensional structures of 1. nanometric or micrometric dimensions, in particular of surfaces from which there rise wherein the three-dimensional structures are surface projections having a height of up to 500 microns arranged according to definite and having defined geometries, wherein it the method comprises the following steps:
- -(a) obtaining of a photopolymeric or UV photopolymerizable mixture including nanoparticles orientable in space;
 - -(b) deposition of a layer of the mixture on a respective substrate to form a layer;
- -(c) exposure of the layer to UV-radiation and control of the polymerization by means of variation of the index of refraction of the layer;
- -(d) application of a magnetic and/or electrical field to the layer capable of producing to produce a desired orientation or positioning of the nanoparticles in orderand to induce the growth of surface projections from the layer; and
 - (e) polymerization of the mixture,

wherein the nanometric dimensions are dimensions from about 50 nm to 1 µm, and the micrometric dimensions are dimensions from about 50 µm to about 500 µm.

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/656,124

- (currently amended): The method according to Claim 1, in which wherein the 2. exposure of the layer to UV-radiation is concomitant with the application of the magnetic and/or electrical field.
- 3. (currently amended): The method according to Claim 1, in which wherein the exposure of the layer of the mixture to UV-radiation and the application of the magnetic and/or electrical field occur in inert an oxygen-free environment, i.e., without oxygen.
- (currently amended): The method according to Claim 1, in which wherein the UV 4. radiation is localized in the areas in which the surface projections must are to be madeformed.
- 5. (currently amended): The method according to Claim 4, in which wherein the UV radiation is localized by means of a binary mask or a half-tone mask.
- (currently amended): The method according to Claim 1, in which wherein the 6. layer is exposed to non-uniform UV radiation, with a consequent non-uniformity in the formation of the polymeric lattice between areas of the layer most illuminated by UV radiation and areas of the layer least illuminated by UV radiation.
- 7. (currently amended): The method according to Claim 6, in which there envisaged wherein the control of polymerization is carried out by detection of the variation of the index

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/656,124

refraction of the layer in the areas with different degrees of cross-linking and the consequent modification of the intensity of the magnetic or electrical field.

- 8. (currently amended): The method according to Claim 1, wherein the exposure of the layer (M) to UV-radiation is envisaged for obtaining a pre-polymerization of the mixture, i.e., a transformation of said transforms the mixture from a liquid state to a gelatinous state.
- 9. (currently amended): The method, according to Claim 8, wherein there is envisaged the application of a magnetic and/or electrical field is carried out by application of a localized magnetic field by means of a magnetic tip-positionable according to a number of axes adjacent to the layer of mixture.
- (currently amended): The method according to Claim 9, in which wherein the tip 10. has a nanometric dimensions, is made of silicon, and is coated with a magnetic film, wherein the nanometric dimension is a dimension of 20-30 nm.
- (currently amended): The method according to Claim 1, in which wherein the 11. polymerization of the mixture is obtained carried out by means of exposure thereof to UV radiation in the absence of application of the magnetic and/or electrical field.

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/656,124

12. (currently amended): The method according to Claim 11, in which wherein the polymerization of the mixture is obtained carried out by means of localized exposure of the projections to UV radiation in the absence of the magnetic and/or electrical field.

- provided means for wherein the polymerization of the mixture is carried out by focusing a beam of UV radiation in the proximity of the tip in order-to enable cross-linking of a-the projections previously formed by the tip itself.
- 14. (currently amended): The method according to Claim 1, in which wherein the is of photopolymeric or UVphotopolymerizable mixture comprises acrylated oligomers and monomers.
- 15. (currently amended): The method according to Claim 1, in which wherein the orientable nanoparticles are selected in-from the group consisting of ferrofluids, electrorheological materials, liquid crystals and magneto-rheological materials.
- 16. (withdrawn): A solid component having three-dimensional surface structures of nanometric or micrometric dimensions, in particular having one or more surfaces in which there are defined projections having a height of up to 500 micron arranged according to definite geometries, obtained in accordance with the method according to claim 1.

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/656,124

17. (withdrawn): A solid component having at least one surface from which there

rise projections having a height of up to 500 micron arranged according to definite geometries,

wherein it is at least in part made using a photopolymer to which are added nanoparticles

orientable in space by means of magnetic and/or electrical fields, the concentration of orientable

nanoparticles being greater at the projections.

18. (withdrawn): The component according to Claim 17, in which the photopolymer

has a base of oligomers and monomers.

19. (withdrawn): The component according to Claim 17, in which the orientable

nanoparticles are selected in the group consisting of ferrofluids, electro-rheological materials,

liquid crystals and magneto-rheological materials.

20. (withdrawn): An apparatus for the implementation of the method according to

Claim 1.

21. (withdrawn): The apparatus according to Claim 20, comprising:

a support for deposition of a layer of a photopolymeric or UV mixture including

nanoparticles orientable in space;

- means for exposing the layer to UV-radiation;

6

AMENDMENT UNDER 37 C.F.R. § 1.111

U.S. Application No.: 10/656,124

means for controlling the polymerization of the mixture by means of variation of its index of refraction;

- means for applying a magnetic and/or electrical field capable of producing a desired orientation or positioning of the nanoparticles of the mixture in order to induce the growth of surface projections from the layer; and

- means for carrying out polymerization of the mixture.